

**CONTINUOUS SLOPED PHASE EDGE  
ARCHITECTURE FABRICATION TECHNIQUE  
USING ELECTRON OR OPTICAL BEAM BLUR FOR  
SINGLE PHASE SHIFT MASK RET**

**ABSTRACT OF THE DISCLOSURE**

[0022] A phase shift mask may include boundaries between phase shift regions with continuous sloped phase edges. The continuous sloped phase edges may be produced by introducing a predetermined degree of defocus into a beam used during production of the mask to image the pattern on the mask. Such a phase shift mask may be "trimless", i.e., not require a corresponding binary "trim" mask for a second exposure to remove phase conflicts after exposure with the phase shift mask.